Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1 - 109. (Canceled)

110. (New) An exposure apparatus including an exposure region performing an exposure process that irradiates an exposure light on a substrate and a measurement region performing a measurement process to the substrate, the exposure apparatus comprising:

a movable member that holds the substrate and moves between the exposure region and the measurement region;

an optical member provided at the exposure region that irradiates the exposure light to the substrate;

a measurement device provided at the measurement region that measures the substrate; and

a prevent device which prevents gas in the exposure region from flowing into the measurement region, wherein

gas that contacts the substrate changing from gas in the measurement region to the gas in the exposure region according to the movement of the movable member.

111. (New) The exposure apparatus according to Claim 110, wherein

the prevent device sets the environment conditions of the exposure region or the measurement region or both regions.

112. (New) The exposure apparatus according to Claim 111, wherein

the environment conditions includes cleanliness or temperature or pressure or humidity or any combination of these.

113. (New) The exposure apparatus according to Claim 111, wherein

the prevent device is an air conditioning device.

114. (New) The exposure apparatus according to Claim 110, wherein

a gas flow control member controls direction of a flow of gas so that movement of the gas from the exposure region to the measurement region is minimized.

115. (New) The exposure apparatus according to Claim 114, wherein

the gas flow control member comprises:

a chamber, which includes the exposure region and the measurement region, and

a blower that makes gas within the chamber flow from the measurement region toward the exposure region.

116. (New) The exposure apparatus according to Claim 115, wherein

the blower comprises:

an intake port formed on the measurement region, and

an exhaust port formed on the exposure region.

117. (New) The exposure apparatus according to Claim 116, wherein

the blower flows gas from the intake port toward the exhaust port along a surface that the movable member moves thereon.

118. (New) The exposure apparatus according to Claim 110, wherein

the prevent device includes a suction device that suctions gas of the exposure region.

119. (New) The exposure apparatus according to Claim 110, wherein

the prevent device prevents the gas from moving from the exposure region to the measurement region.

120. (New) The exposure apparatus according to Claim 119, wherein

the substrate is exposed to the exposure light via a liquid.

121. (New) The exposure apparatus according to Claim 120, further comprising:

an immersion device that forms an immersion area partially between the substrate and the optical member, the immersion device is disposed at the exposure region.

122. (New) The exposure apparatus according to Claim 120, wherein

the prevent device prevents the gas affected by the liquid from moving from the exposure region to the measurement region.

123. (New) The exposure apparatus according to Claim 110, further comprising:

a second movable member that moves between the exposure region and the measurement region, the second movable member moving independently from the movable member.

124. (New) The exposure apparatus according to Claim 123, wherein

the second movable member holds a substrate.

125. (New) The exposure apparatus according to Claim 123, wherein

the movable member and the second movable member are supported by a same base.

126. (New) A device manufacturing method that includes a lithography process, wherein

the exposure apparatus of Claim 110 is used in the lithography process.

127. (New) The exposure apparatus according to Claim 110, wherein

the substrate is held by the movable member so that the substrate contacts the gas in a movement path of the movable member.

128. (New) The exposure apparatus according to Claim 120, wherein

the measurement is performed at the measurement region without a liquid on the substrate.

129. (New) The exposure apparatus according to Claim 120, wherein

the gas in the exposure region has higher humidity than the gas in the measurement region.

130. (New) The exposure apparatus according to Claim 124, wherein

a process of the exposure for a substrate held by the movable member and a process of measurement for a substrate held by the second movable member are performed simultaneously.

131. (New) An exposure method for an exposure apparatus including an exposure region which performs an exposure process that irradiates an exposure light on a substrate and a measurement region which performs a measurement process to the substrate, the exposure method comprising:

measuring the substrate in a state in which the substrate contacts gas in the measurement region;

irradiating the exposure light to the substrate from an optical member provided at the exposure region;

moving the substrate between the exposure region and the measurement region;

preventing gas in the exposure region from flowing into the measurement region, wherein

gas that contacts the substrate changing from the gas in the measurement region to the gas in the exposure region according to the movement of the movable member and the substrate is irradiated by the exposure light by the optical member at the exposure region.

132. (New) The exposure method according to Claim 131, wherein

the substrate is irradiated by the exposure light through the optical member and a liquid at the exposure region.

133. (New) The exposure method according to Claim 132, wherein

the measurement is performed at the measurement region without a liquid on the substrate.

134. (New) The exposure method according to Claim 131, wherein

a process of the exposure for a substrate held by a first movable member and a process of measurement for a substrate held by a second movable member are performed simultaneously.

135. (New) The exposure method according to Claim 131, wherein

preventing the gas in the exposure region from flowing by using a ventilation system that controls an environment of the exposure region or the measurement region.

136. (New) A device manufacturing method that includes a lithography process, wherein

an exposure method of Claim 131 is used in the lithography process.